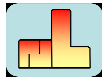
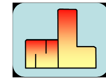
 2nd Spanish Workshop on Nanolithography 

Campus de la Universitat Autònoma de Barcelona, Bellaterra, Barcelona
November 10th-13th, 2008

Second Spanish Workshop on Nanolithography

(Nanolithography, nanopatterning, self-assembly, atomic and molecular manipulation, and their applications)

Background

After a successful first edition in Zaragoza in October 2007, the second Spanish Workshop on Nanolithography and their applications will serve as a meeting place for the Spanish community working in this field together with few European colleagues experts in the programmed topics. The workshop primarily aims at gathering scientists interested in nanolithography and their applications.

The workshop will contain invited and oral presentations, posters and demonstrations / tutorials on 'state of the art' nanolithography equipment available in campus.

Topic sessions

a) Ion and electron beam lithography
   Including, nanolithography, nanopatterning, instrumentation)-

b) Sanning Probe Microscopy based nano-lithography
   (including, local anodic oxidation, dip-pen nanolithography, atomic and molecular manipulation)

c) Nanoimprint lithography
   (including thermal nanoimprint, hot embossing, UV-Nanoimprint, reverse nanoimprint)

d) Soft lithography and μ-contact printing

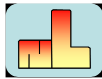
e) Lithography guided self assembly

f) Emerging nanopatterning methods (nanostencil lithography, nano-templates for pattern transfer,

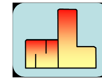
g) Resists for nanolithography

Organizers

Francesc Pérez-Murano
(Instituto de Microelectrónica de Barcelona, CNM-CSIC)
Teresa Puig
(Instituto de Ciencia de Materiales de Barcelona, ICMAB-CSIC)
Daniel Ruiz-Molina
(Centro de Investigación en Nanociencia y Nanotecnología, CIN2, ICN-CSIC)



2nd Spanish Workshop on Nanolithography



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Key-note and invited speakers

Juergen Brugger	EPFL, Lausanne. Switzerland.	Nanostencil lithography
Elmar Platzgummer	IMS-nano. Austria	Projection maskless patterning
Heiko Wolf	IBM-Zurich. Switzerland	Soft Lithography
Isabelle Berbezier	CRMCN-CNRS, Marseille, France	Self assembly
Pietro Gambardella	CIN2 (ICN-CSIC). Bellaterra. Spain	Atomic manipulation
Nikolaos Kehagias	CIN2 (ICN-CSIC). Bellaterra. Spain	Nanoimprint Lithography
Daniel Maspoch	CIN2 (ICN-CSIC). Bellaterra. Spain	Dip-pen nanolithography
David Mecerreyes	CIDETEC. San Sebastian. Spain	Resists for nanolithogrpahy
Kornelius Nielsch	University of Hamburg. Germany	Self assembly
Helmut Schift	PSI. Villigen. Switzerland	Nanoimprint Lithography
Iwo Utke	EMPA. Lausanne. Switzerland	Electron Beam Lithography

Scientific committee

Ricardo García	IMM-CNM, CSIC	Francesc Pérez-Murano	IMB-CNM, CSIC
Ricardo Ibarra	INA	Teresa Puig	ICMAB-CSIC
Emilio Lora-Tamayo	IMB-CNM, CSIC	Albert Romano-Rodriguez	UB
José Ignacio Martín	Univ. Oviedo	Daniel Ruiz-Molina	CIN2, ICN-CSIC
Elena Martínez	IBEC-UB	Javier Sesé	INA
Santos Merino	TEKNIKER	Jordi Sort	UAB
Isabel Obieta	INASMET	Clivia Sotomayor	CIN2-ICN
Carmen Ocal	ICMAB-CSIC	José María de Teresa	ICMA-CSIC

Workshop structure

The workshop starts on Monday November 10th afternoon and it ends Wednesday afternoon. It features:

1.- Keynote and invited talks.
2.- Oral and Poster presentation.
3.- Commercial Exhibition
4.- Tutorials and practical demonstrations

Deadlines

1st announcement: July 1st
Final announcement: Sept 5th
Abstract Deadline: Sept 22nd
Abstract acceptance: Oct 13th
Registration starting: Oct 1st
Early registration: Oct 31st

Exhibitors and demonstration

FEI
Lot-Oriel
Nanotec
Raith
Veeco
Zeiss

www.icmab.es/nanolitho08/